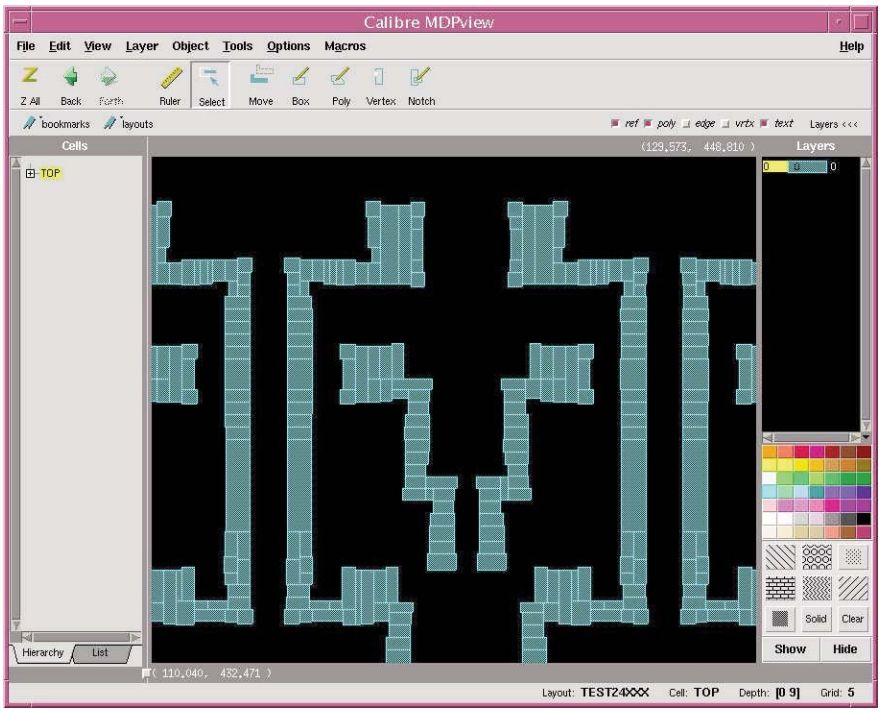
Calibre MDPview

Manufacturability
D A T A S H E E T



Calibre MDPview is the viewing tool for fast display and analysis of GDSII and OASIS files and mask pattern data. It is part of the Calibre MDP tool suite offered by Mentor Graphics. This illustration shows part of a variable shaped beam file.

Calibre MDPview: Visual verification of mask data

Calibre® MDPview builds on Calibre's core competency in physical verification. It provides the capability for quick and easy review of the design data in GDSII and OASIS format as well as in all supported mask writer pattern formats and data assemblies through the respective jobdecks. In this way MDPview complements the Calibre MDP fracture tool portfolio for visual verification tasks and assembly tasks.

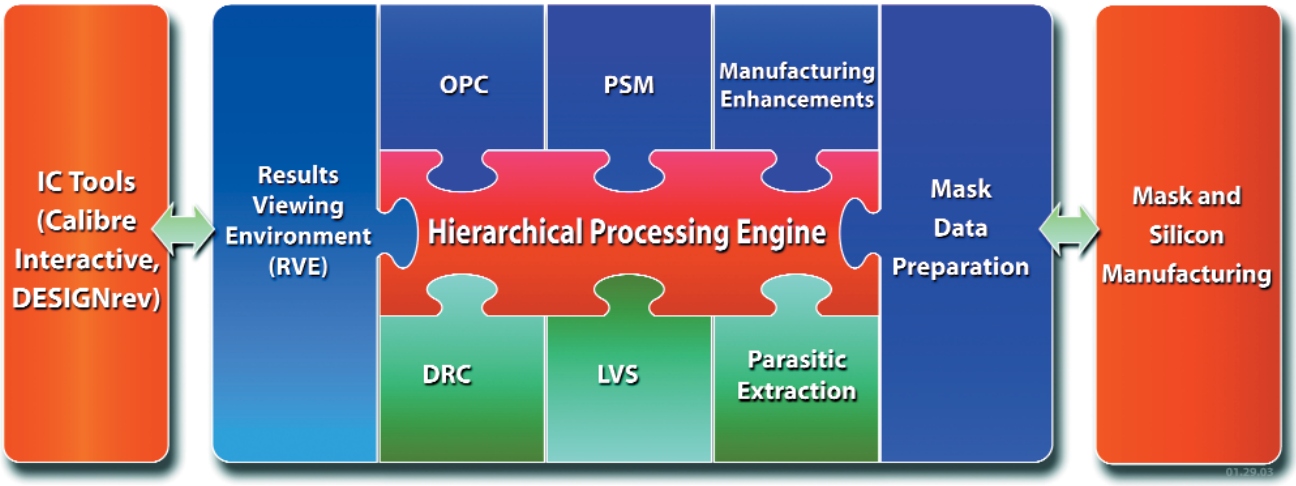
Calibre MDPview can be linked with Calibre RVE, the robust results viewing environment and integrated debugging interface, to guide the user through areas previously identified as problems during the mask rule check executed with MDPverify. The tool will match the location with the displayed layout, zoom-in and then highlight the affected pattern.

Further analysis is enabled by overlay capabilities that allow the user to display and align various files on top of each other. Statistical utilities are available to characterize pattern files.

Macros and scripts can be created and executed in batch mode to customize repeated functions such as the assembly of a number of GDSII input files into a single database.

Key Product Benefits

- Allows viewing of GDSII and OASIS files, plus files and jobdecks of many mask writer formats including MEBES, JEOL, Toshiba/Nuflare, Hitachi and Micronic.
- Provides special viewing modes that visualize the internal structure of the pattern files, e.g. segments and fields.
- Features flexible overlay utility for all file formats and jobdecks.
- Loads multiple layouts at the same time, if desired.
- Enables fast zooming and panning for efficient navigation.
- Operates easily and simply, like a browser.
- Includes rule-based measurement capability.
- Links to Calibre's results viewing environment (RVE) for fast review of mask rule checking results.
- Supports batch-mode layout operations, such as GDS assembly and placement tasks.
- Patternfile information utilities for quick, high-level assessment of pattern files.
- Built-in macro capability for customization of layout functions.



The Calibre tool suite offers a complete design-to-silicon solution to ensure a confident design for manufacturing.

Calibre Offers a Complete Design-to-Silicon Solution

A powerful hierarchical engine is at the heart of the Calibre tool suite, which offers a complete IC and SoC design-to-manufacturing solution. Each tool is an excellent point tool on its own, but the combination of Calibre DRC, Calibre LVS and Calibre RVE (results viewing environment) with Calibre xRC, Calibre LFD, Calibre RET and Calibre MDP, simplifies and strengthens the design flow.

Calibre xRC parasitic extraction tool accurately models the parasitic effects of passive interconnects that can cause design failure in deep submicron IC designs. Automated interfacing of Calibre LVS to Calibre xRC provides simplicity (one rule file, one invocation) and automated back annotation for accurate parasitic extraction results, and ensures accurate and intentional device extraction with parameter calculation and parasitic device extraction for accurate simulation.

Calibre Interactive™ complements the Calibre physical verification tool suite by enabling designers to perform verification from within Cadence® Virtuoso and Mentor Graphics IC Station and Calibre DESIGNrev. Together with Calibre RVE, Calibre Interactive provides a seamless, push-button interface, enabling designers to use a single platform for cell/block and full-chip physical verification.

The Calibre RET tool suite for Optical and Process Correction (OPC), Phase Shift Mask (PSM), Scatter Bars (SB) and Off-Axis Illumination (OAI) deliver silicon accuracy, fastest turn-around-time and excellent yield.

Calibre MDP allows for seamless continuation of the data manipulations required for RET techniques to the mask data format conversion in one batch run, keeping data hierarchically represented as long as possible.

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